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N. DeRiggi

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Kazufumi OGAWA et al.

Serial No.:

09/694,575

Filing Date:

October 24, 2000

For:

METHOD OF MANUFACTURING A

FLUOROCARBON-BASED COATING

**FILM** 

Examiner: Erma Cameron

Group Art Unit: 1762

**RESPONSE UNDER 37 CFR 1.111** 

Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Action mailed October 22, 2002, please re-consider this application in light of the following Remarks.

## **REMARKS**

Claims 12-45 were rejected under 35 USC 112, first paragraph. The Examiner's position is that the Declarations of Mr. Ogawa and Ms. Takano provided in Serial No. 09/112,219 show that the material on a glass substrate having an indium-tin oxide alloy film with the product formed by dissolving 1 weight percent of Cl-(SiCl<sub>2</sub>O<sub>2</sub>)<sub>2</sub>-SiCl<sub>3</sub> in a choloform solvent is silicon dioxide, not a siloxane as recited in the claims. This rejection is respectfully traversed.